

PATENT
1752-0147P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: FUJIYAMA, Takeshi et al Conf.:
Int'l. Appl. No.: PCT/JP00/01955
Appl. No.: NEW Group:
Filed: September 28, 2001 Examiner:
For: SILICONE RESINS AND PHOTSENSITIVE
RESIN COMPOSITIONS CONTAINING THE
SAME

3/A
C7
7/27/03

PRELIMINARY AMENDMENT

BOX PATENT APPLICATION

Assistant Commissioner for Patents
Washington, DC 20231

September 28, 2001

Sir:

The following Preliminary Amendments and Remarks are respectfully submitted in connection with the above-identified application.

IN THE SPECIFICATION:

Before line 1, insert [This application is the national phase under 35 U.S.C. § 371 of PCT International Application No. PCT/JP00/01955 which has an International filing date of March 29, 2000, which designated the United States of America.]

0937598-092601

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